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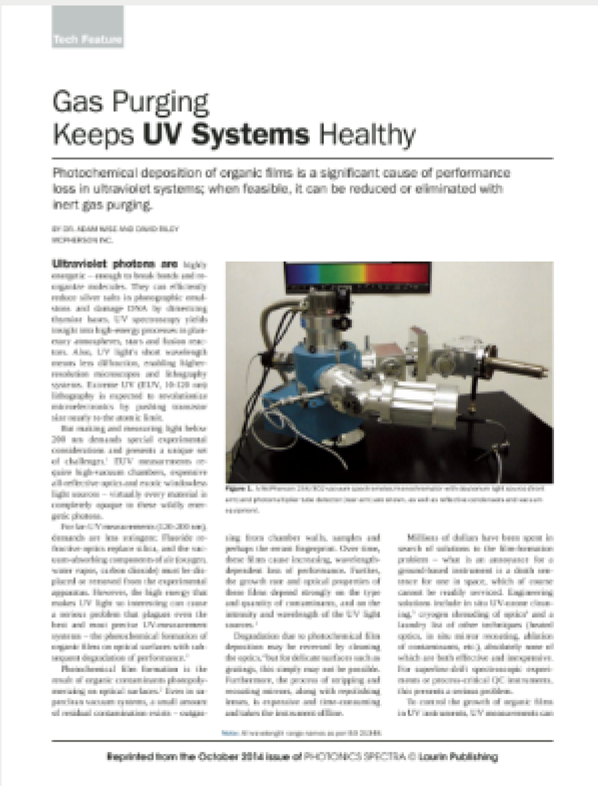
Tech Feature

Gas Purging Keeps **UV Systems** Healthy

Photochemical deposition of organic films is a significant cause of performance loss in ultraviolet systems; when feasible, it can be reduced or eliminated with inert gas purging.

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Gas Purging Keeps UV Spectrophotometers Healthy

Measuring in the far-UV (FUV) 120-220 nm presents unique challenges. The high energy that makes UV light interesting can cause photochemical formation of organic films on optical surfaces. These films cause increasing, wavelength-dependent loss of performance. To control the growth of organic films, UV measurements can be made in an inert gas atmosphere (typically nitrogen) rather than under vacuum. Nitrogen gas in UV spectrophotometers reduces contaminant desorption and photopolymerization, without decreasing optical performance.

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